

Notice of References Cited

Application/Control No.

10/595,640

Applicant(s)/Patent Under

Reexamination

TSUBATA ET AL.

Examiner

EARL N. TAYLOR

Art Unit

2818

Page 1 of 1

U.S. PATENT DOCUMENTS

*	Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
*	A US-2005/0223986 A1	10-2005	Choi et al.	118/715
*	B US-2002/0117691 A1	08-2002	Choi et al.	257/225
*	C US-5,712,208	01-1998	Tseng et al.	438/770
D	US-			
E	US-			
F	US-			
G	US-			
H	US-			
I	US-			
J	US-			
K	US-			
L	US-			
M	US-			

FOREIGN PATENT DOCUMENTS

*	Document Number Country Code-Number-Kind Code	Date MM-YYYY	Country	Name	Classification
N					
O					
P					
Q					
R					
S					
T					

NON-PATENT DOCUMENTS

*	Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
U	Wolf and Tauber; 6.5 Properties and Chemical Vapor Deposition of Silicon Nitride, Silicon Processing for the VLSI Era, Volume 1 - Process Technology Second Edition, 2000, pages 202-206
V	
W	
X	

*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a))
Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.